

IN THE SPECIFICATION:

Please amend paragraph [0038] as follows:

[0038] FIG. 10 illustrates a geometric method for mitigating sidelobe artifacts in a radiation-patterning process, in accordance with an embodiment of the present invention. The present method generates a mathematical method or construct 64 that includes design features 66. One methodology of the present invention determines which features 66 are adjacent to other features 66 and within a threshold spatial distance of one another. Design features 66 ultimately correspond[[s]] to elements of a radiation-patterning tool that may be used for printing one or more patterns on a radiation-sensitive material. As interference is a function of the additive effects of radiation, a zone or ring is defined by a radius around each ~~about the~~ feature where other adjacent radiation could pose an additive effect. The threshold spatial distance utilized in identifying design features in the present methodology is about eight-tenths of the wavelength divided by the numerical aperture.